	Θ <sub>adv</sub> (deg) (-Br)	$\Theta_{adv}$ (deg) (–NH <sub>2</sub> )	Θ <sub>adv</sub> (deg)(-CH <sub>3</sub> )
	87.9 ± 2.9	$69.5 \pm 3.6$	$108.3 \pm 3.1$
Exposure Condition	After Exposure	After Exposure	After Exposure
Acetone	84.9 ± 1.2	$65.3 \pm 1.7$	$109.1 \pm 2.1$
IPA	88.9 ± 0.9	$68.4 \pm 1.8$	$109.1 \pm 2.1$

 Table S1. CA measurements of pre- and after solvent exposure conditions for bromo-,

 amino-, and methyl terminated glass surfaces.

	Θ <sub>adv</sub> (deg) (–Br)	$\Theta_{adv}$ (deg) (-NH <sub>2</sub> )	Θ <sub>adv</sub> (deg)(– CH <sub>3</sub> )
	87.9 ± 2.9	$69.5 \pm 3.6$	$108.3 \pm 3.1$
Exposure Condition	After Exposure	After Exposure	After Exposure
$100 \text{ mJ/cm}^2$	89.8 ± 0.9	69.7 ± 1.9	$108.3 \pm 6.6$
$200 \text{ mJ/cm}^2$	84.4 ± 1.2	$67.0 \pm 0.9$	$106.0 \pm 1.0$
$500 \text{ mJ/cm}^2$	86.7 ± 2.1	$70.5 \pm 2.0$	$105.8 \pm 1.1$
$1000 \text{ mJ/cm}^2$	$87.8 \pm 0.4$	$70.2 \pm 0.5$	$106.0 \pm 1.3$
$1500 \text{ mJ/cm}^2$	$84.4 \pm 0.3$	$65.3 \pm 1.1$	$110.2 \pm 1.2$

**Table S2.** CA measurements of pre- and after UV light exposure conditions for bromo-,amino-, and methyl terminated glass surfaces.



**Figure S1.** The AFM micrographs of a) bromo- terminated surface, b) bromo- terminated surface after Au etchant exposure, c) bromo- terminated surface after HCl acid exposure, d) bromo- terminated surface after sulfuric acid exposure. Detailed discussions about implications for changes in surface roughness can be found in the main manuscript.